

(Rev. 5/92)

FORM PTO-1449 SAMUELS, GAUTHIER & STEVENS LLP 225 Franklin Street, Boston, MA 02110 Telephone: (617) 426-9180

> INFORMATION DISCLOSURE STATEMENT BY APPLICANT

ATTORNEY DOCKET NO.5342b

Eugene A. Fitzgerald APPLICANT

<u>Herewith</u> FILING DATE SERIAL NO._

<u>Unknown</u> GROUP

Unknown **EXAMINER**



U.S. PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TTN	AA	5,208,182	5/4/93	Narayan et al.	438	509	11/12/91
TTN	AB	5,252,173	10/12/93	Inoue	438	509	11/22/91
TTN	AC	5,279,687	01/18/94	Tuppen et al.	148	33.2	02/27/90
TTU	AD	6,117,750	09/12/00	Bensahel et al.	438	478	12/21/98
TIN	AE	5,210,052	05/11/93	Takasaki	438	509	05/13/92
777	AE	5,221,413	06/22/93	Brasen et al.	117	89	04/24/91
177	AG	5,308,444	05/03/94	Fitzgerald, Jr. et al.	117	90	05/28/93
TTN	AH	5,442,205	08/15/95	Brasen et al.	257	191	09/09/93
TTN	AI	5,810,924	09/22/98	Legoues et al.	117	89	06/07/95
TTN	AJ	6,107,653	08/22/00	Fitzgerald	257	191	06/23/98

FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
TTN	AK	63073398	3/29/88	Japan			yes (abstract)
	AL						
	AM						
	AN				No.		
	AO						

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL		
TTN	AP	"Relaxed Ge _x Si _{1-x} structures for III-V integration with Si and high mobility two-dimensional electron gases in Si"; by Fitzgerald et al. 1992 American Vacuum society; pages 1807-1819
TTN	AQ	"GeSi/Si NANOSTRUCTURES" by E.A. Fitzgerald; Department of Materials Science, Massachusetts Institute of Technology (1995) pgs; 1-15

EXAMINER

DATE CONSIDERED ON 131/2002

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Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant. Telephone: (617) 426-9180

PRORMATION DISCLOSURE STATEMENT BY APPLICANT

5342B ATTORNEY DOCKET NO

Eugene A. Fitzgerald APPLICANT

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U.S. PATENT DOCUMENTS

EXAMINER INITIAL \		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
TN	AA	4,900,372	02/13/1990	Lee et al.	148	33.4	03/02/1989
	AB						
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FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
	AK						
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	AM						
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

EXAMINER INITIAL		
	AP	Hsin-Chiao Luan et al., "High-quality Ge epilayers on Si with low threading-dislocation densities," <i>Applied Physics Letters</i> , American Institute of Physics, New York, Vol, 75, No. 19, November 8, 1999, pages 2909-2911.
	AQ	

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Sheet 1 of 1

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